

## References

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## Vitae

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### Conference Presentation:

1. Pattira Homhoul, Sukkaneste Tungasmita, Surasing Chaiyakunand Chakapan Thawornkira, "The Effect of Growth Temperature on the Structure of Chromium Nitride Thin Films" *31<sup>st</sup> Congress on Science and Technology of Thailand (STT 2004)*, Suranaree University of Technology, Thailand, October 18-20, 2005.

2. Pattira Homhoul, Sukkaneste Tungasmita, Surasing Chaiyakunand Chakapan Thawornkira, "The Effect of Growth Temperature on the Structure of Chromium Nitride Thin Films" *14<sup>th</sup> Academic conference*, Faculty of Science, Chulalongkorn University, Thailand, March 16-17, 2005.

